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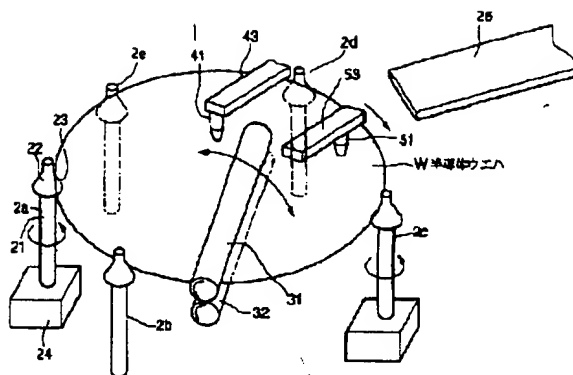
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TITLE : CLEANER



ABSTRACT : PROBLEM TO BE SOLVED: To provide a cleaner for cleaning not only the central part but also the circumferential edge part of a wafer, when a substrate such as a wafer is cleaned.

SOLUTION: A wafer (W) is held horizontal by a rotation guide member 2. A circumferential edge part of the wafer (W) is sent out in a circumferential direction by the rotation guiding member 2, and the wafer (W) is rotated. The cleaner includes cleaning brushes 31 and 32 for cleaning the wafer (W), main nozzles 41 and 42 for supplying a cleaning solution to a central part of the rotating wafer (W), and auxiliary nozzles 51 and 52 for supplying the cleaning solution to a boundary edge part of the wafer (W). Mega-sonic nozzles are used as the auxiliary nozzles 51 and 52 for feeding a cleaning solution to which vibration is transmitted by ultrasonic wave. Then, the wafer (W) and the brushes 31 and 32 are vibrated, and the wafer (W) is cleaned. The vibration imparted cleaning solution enters a gap between the rotation guiding member 2 and the wafer (W), and as a result, the boundary edge part and the edge face of the wafer (W) are cleaned.

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